

# NbN Thin Films: Growth and Characterization

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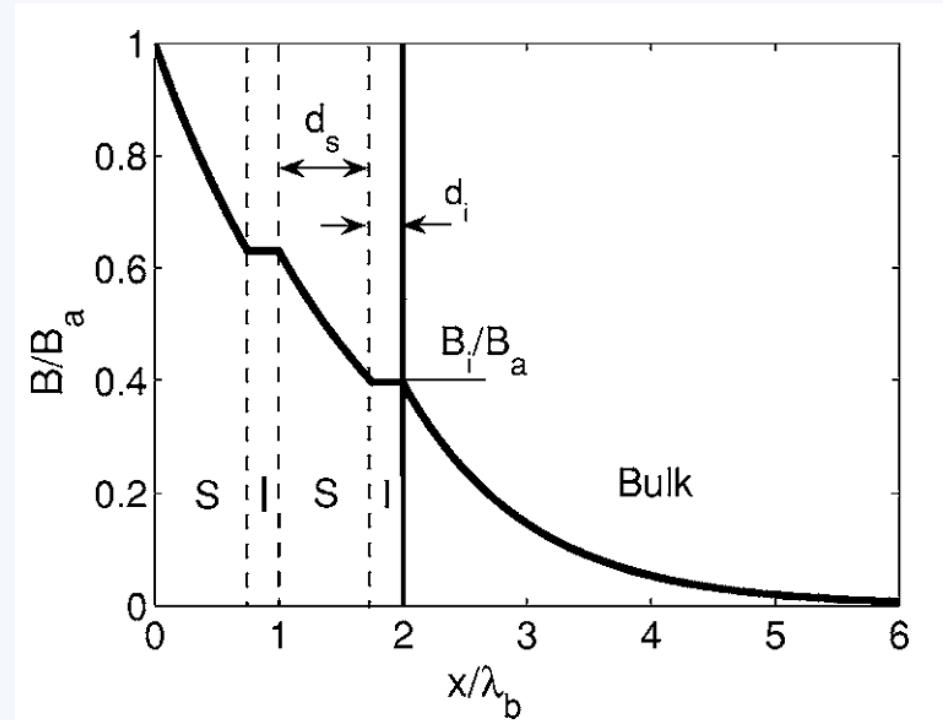
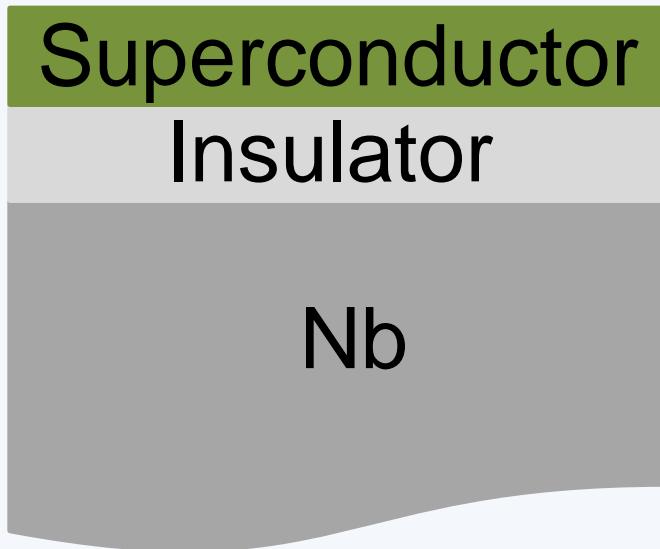
Anne-Marie Valente-Feliciano

Josh Spradlin

# Outline

- Motivation
- NbN/MgO(100) Thin Films
  - Surface Morphology (AFM)
  - Structure (XRD, RRR)
  - Superconducting Properties (SQUID)
- Multilayer Films
- Conclusions and Future Work

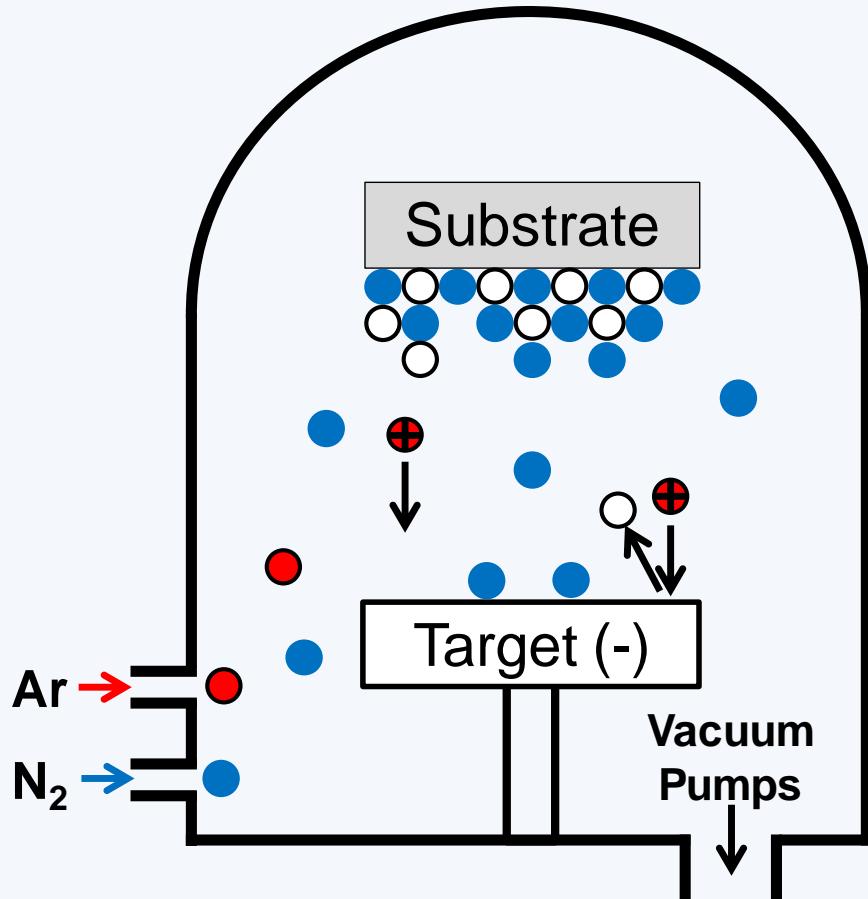
# Can new materials push performance limits?



A. Gurevich, *Appl. Phys. Lett.* **88**, 012511 (2006).

Higher critical field → Higher accelerating gradient of interest in defense as well as scientific applications.

# DC Reactive Sputter Deposition



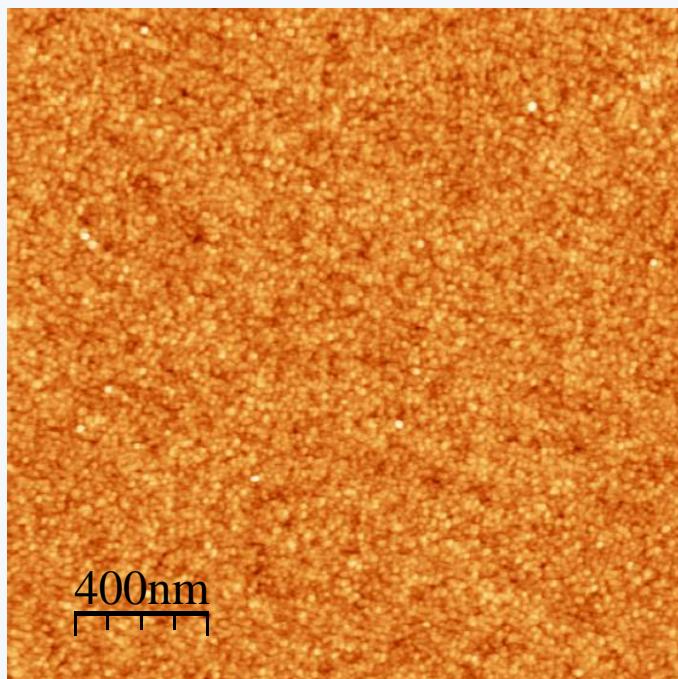
Ar:N<sub>2</sub> ratio affects film structure and properties

Fixed total pressure at 3.4 mTorr

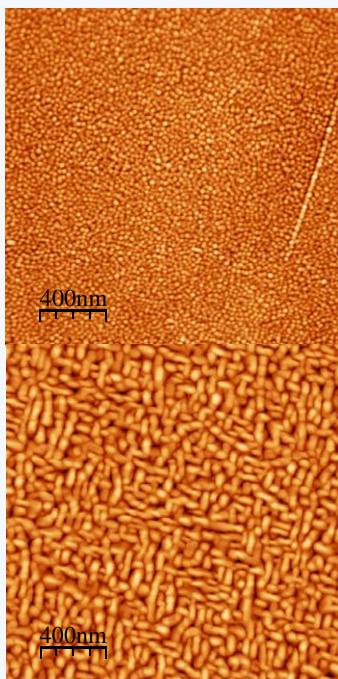
Varied partial pressures

# Surface Morphology

NbN

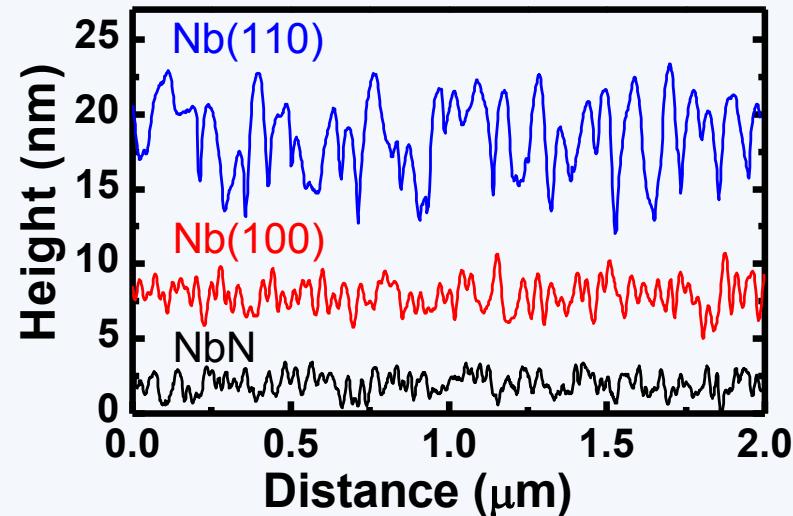


Nb(100)

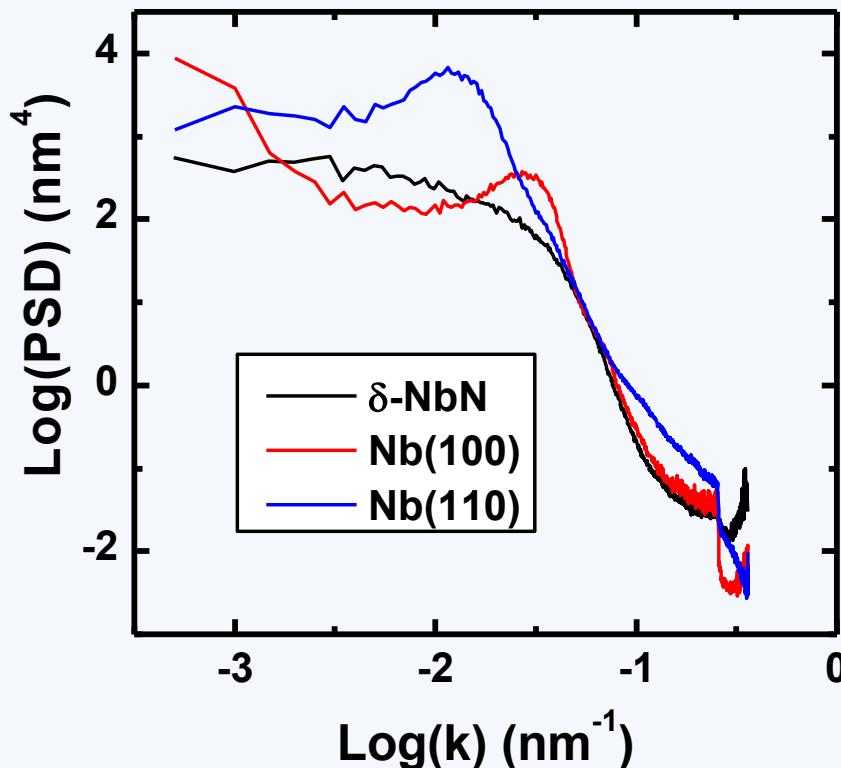
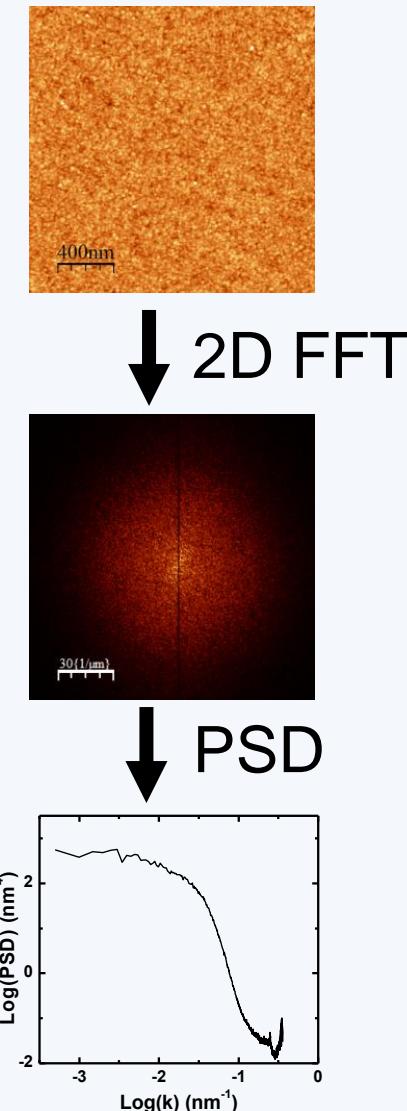


Nb(110)

RMS Roughness for comparable film thickness:  
200 nm NbN <1 nm  
100 nm Nb(100) 1.21 nm  
100 nm Nb(110) 2.45 nm



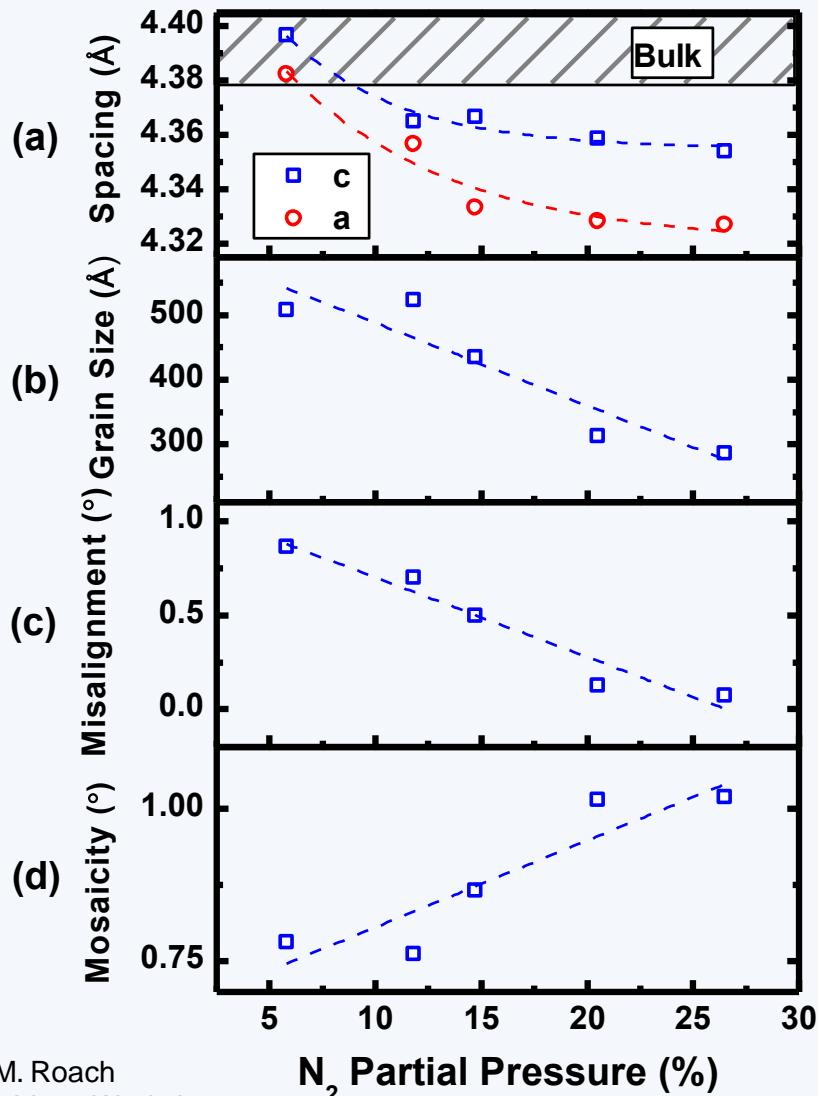
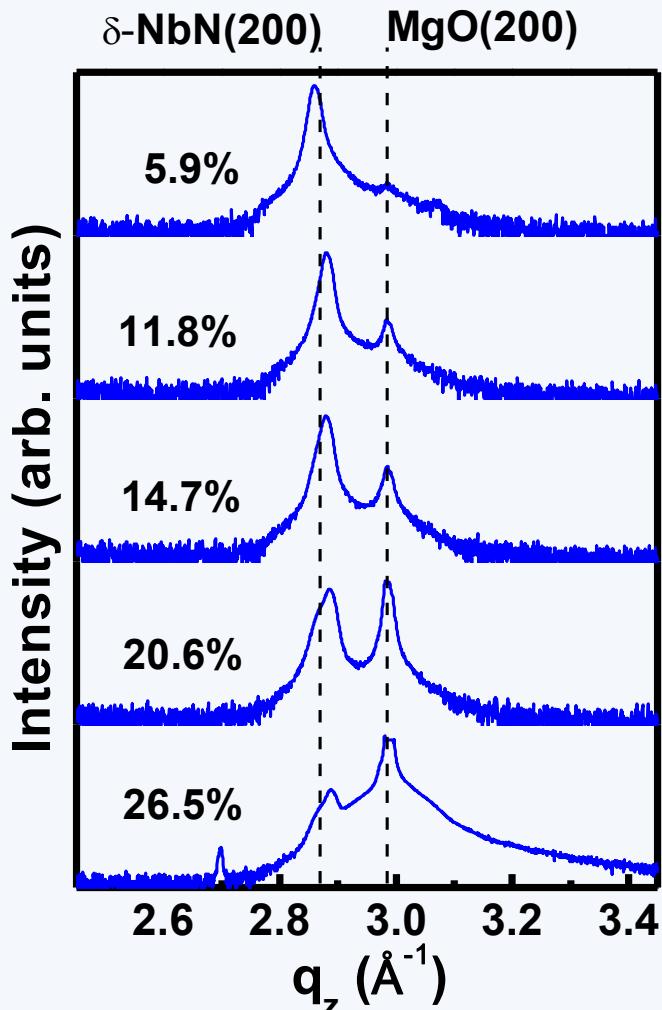
# Surface Morphology



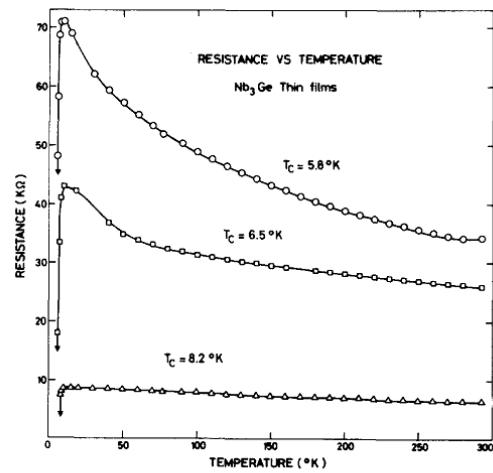
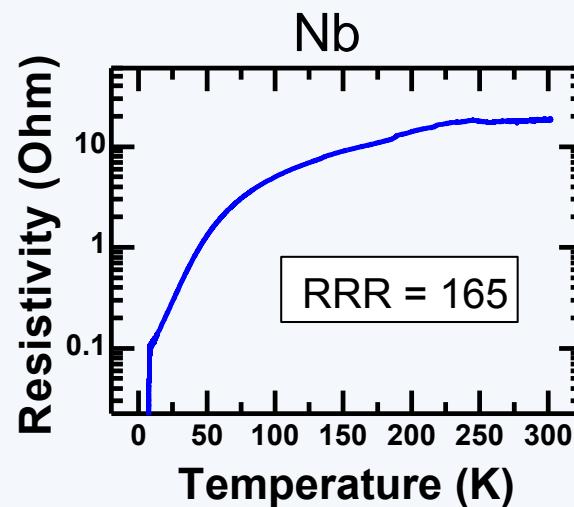
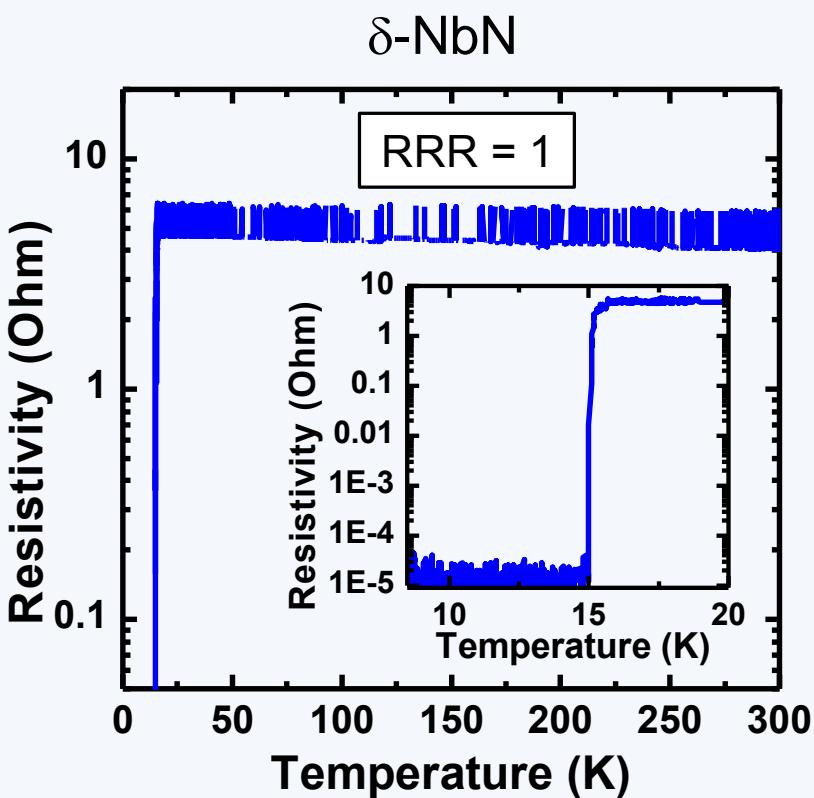
Peaks present in Nb PSD indicate wavelength selection and influence of step edge barrier

Absence of peaks for NbN PSD characteristic of self affine growth

# Film Structure



# Residual Resistance Ratio

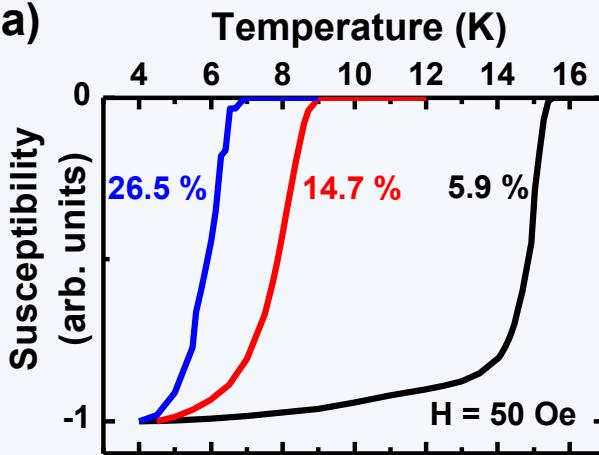


H. C. Jones, Appl. Phys.  
Lett. **27**, 471 (1975)

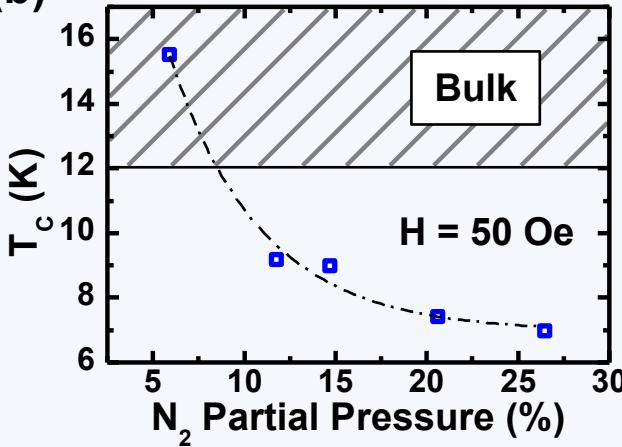
FIG. 1. Resistance of  $\text{Nb}_3\text{Ge}$  as a function of temperature. The superconducting critical temperature is lower the faster the resistance increases as the temperature decreases.

# Superconducting Properties

(a)

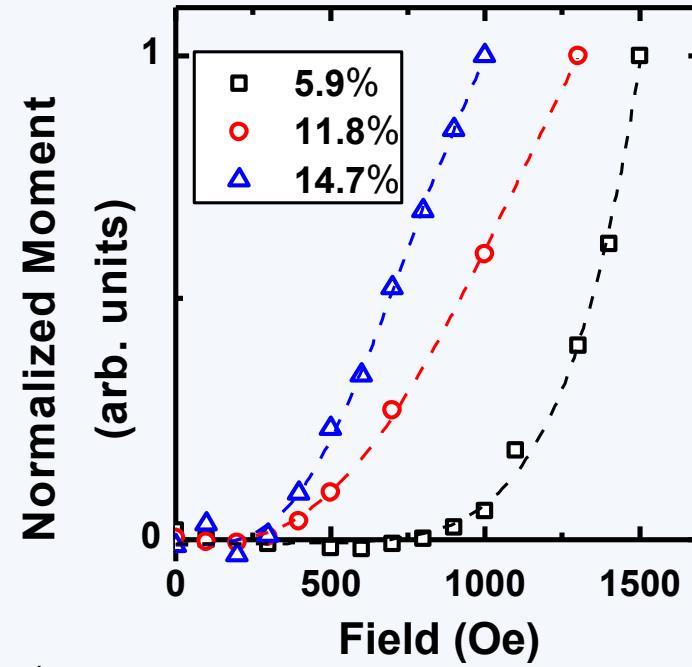


(b)

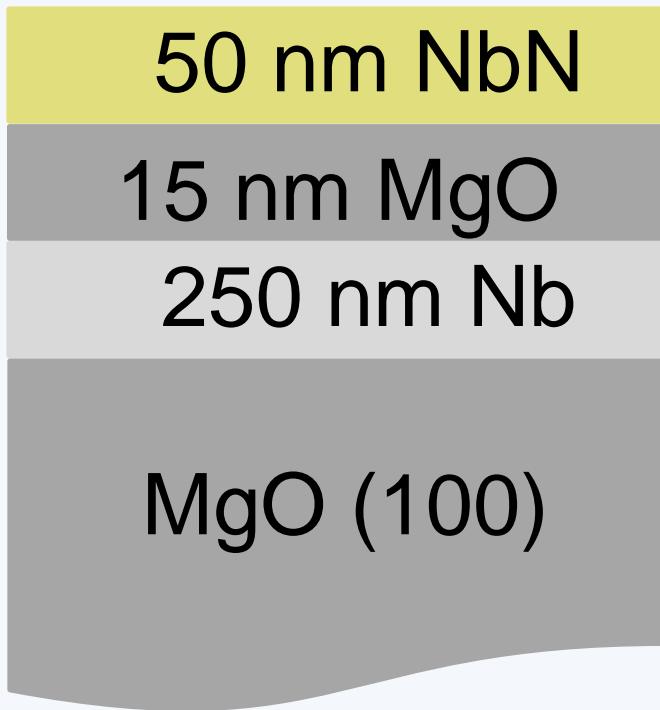


$H_{C1}$  determined by measuring trapped moments that appear after application and removal of  $H \geq H_{C1}$

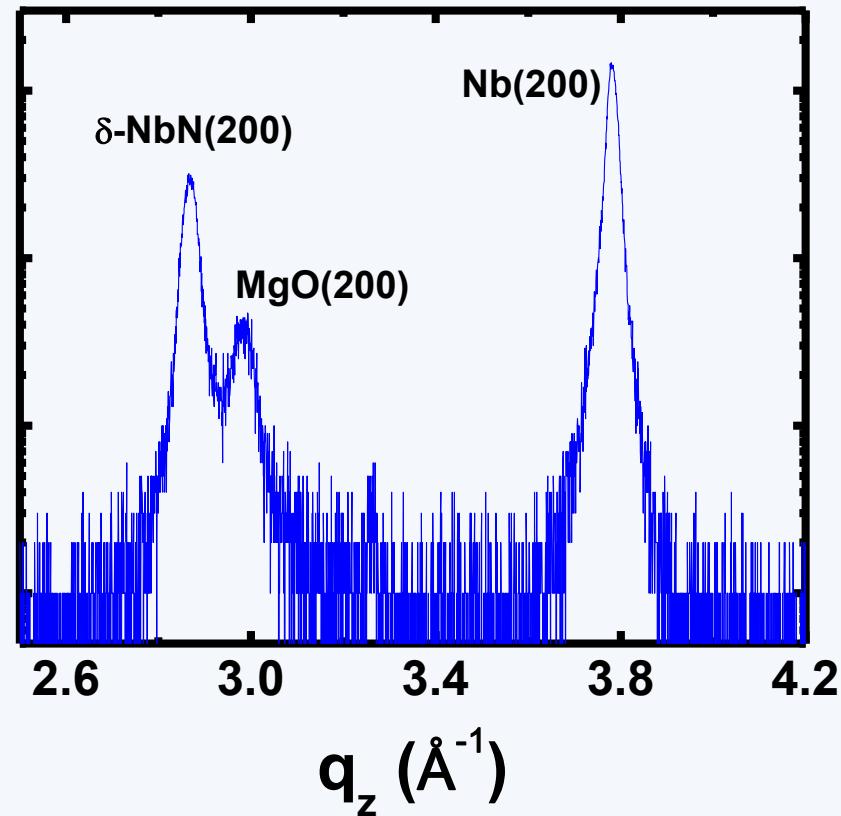
C. Böhmer, G. Brandstätter, and H. W. Weber, Supercond. Sci. Technol. **10** A1 (1997).



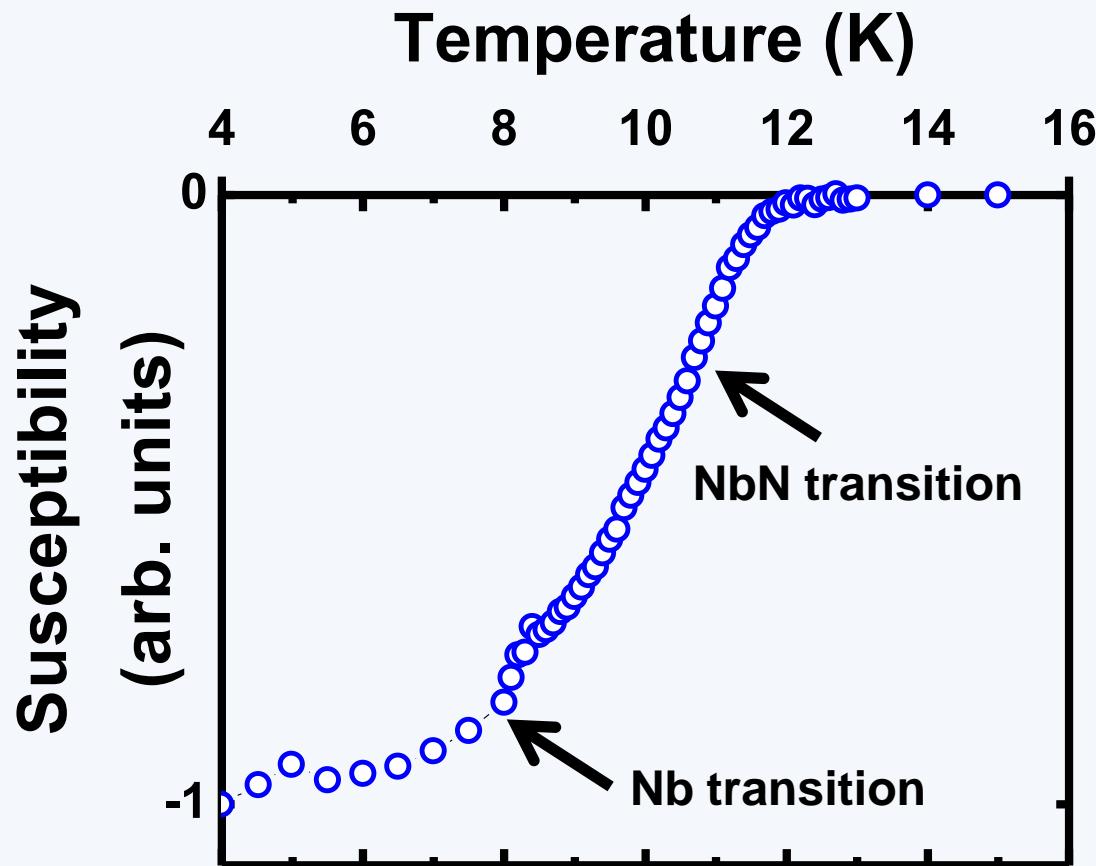
# Multilayer Film



Intensity  
(arb. units)



# Multilayer Film



- Further optimization
  - Surface modification (ion gun)
  - Alternative insulators (AlN)

# Conclusion

- Produced high quality NbN films in ideal situation
- NbN differs from Nb in surface morphology and resistive behavior
- Multilayer optimization in progress
- RF measurements
- Investigate other materials